

**AMENDMENT UNDER 37 C.F.R § 1.116  
EXPEDITED PROSECUTION - ART GROUP 1795**

03500.518677

PATENT APPLICATION

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Application of:	)	
SHOJI SHIBA, ET AL.	:	Examiner: Anca Eoff
Application No.: 10/577,218	)	Group Art Unit: 1795
Filed: April 26, 2006	:	Confirmation No.: 3411
For: PHOTORESISTIVE RESIN	:	
COMPOSITION, METHOD OF	)	
FORMING LEVEL DIFFERENCE	:	
PATTERN USING THE	)	
PHOTORESISTIVE RESIN	:	
COMPOSITION, AND METHOD	)	
OF PRODUCING INK JET HEAD	:	Date: December 16, 2008

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**AMENDMENT AFTER FINAL REJECTION**

Sir:

a) Introductory Comments:

In response to the final Official Action dated September 18, 2008, kindly amend the above-identified application as follows.